

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Cyril Cabral, Jr., et al. **Examiner:** Long Pham
Serial No: 10/662,900 **Art Unit:** 2814
Filed: September 15, 2003 **Docket:** YOR920030218US1(16714)
For: REDUCTION OF SILICIDE FORMATION TEMPERATURE ON
SiGe CONTAINING SUBSTRATES
Confirmation No: 1278 **Dated:** December 21, 2006

Mail Stop AF
Commissioner for Patents
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RESPONSE UNDER 37 C.F.R. § 1.116

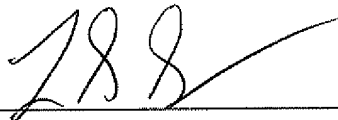
Sir:

In response to the Office Action dated October 24, 2006, applicants submit the following amendments and remarks for entry into the record of the above-identified patent application.

CERTIFICATION OF ELECTRONIC TRANSMISSION

I hereby certify that this document is being filed in the United States Patent and Trademark Office on the date shown below via electronic transmission.

Dated: December 21, 2006



Leslie S. Szivos, Ph.D.